

Structure and Composition of the Atmosphere

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Properties of the Atmosphere

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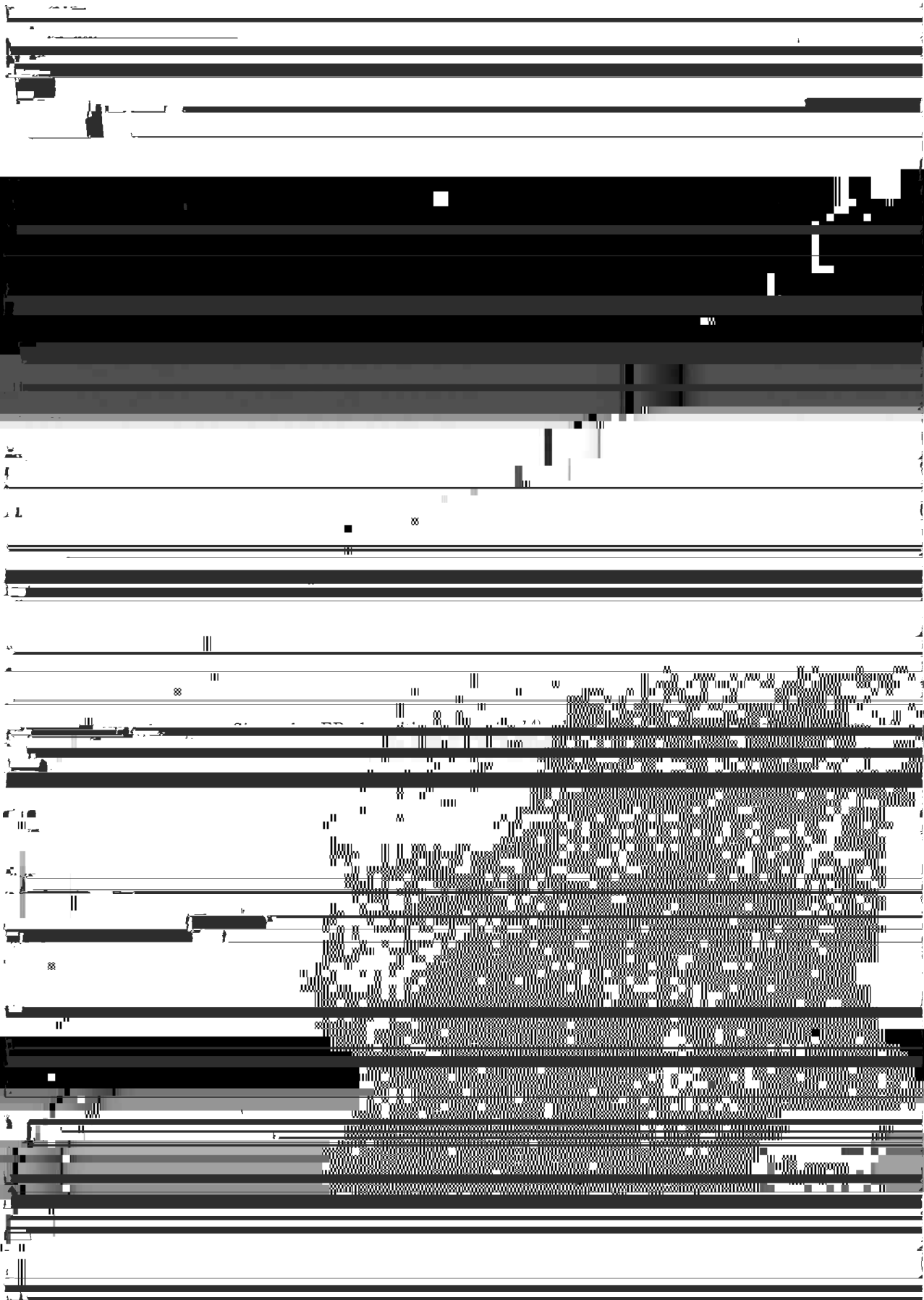
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1. 4. 2. The ... end to the 111 spot of the pine blende one. Shun...



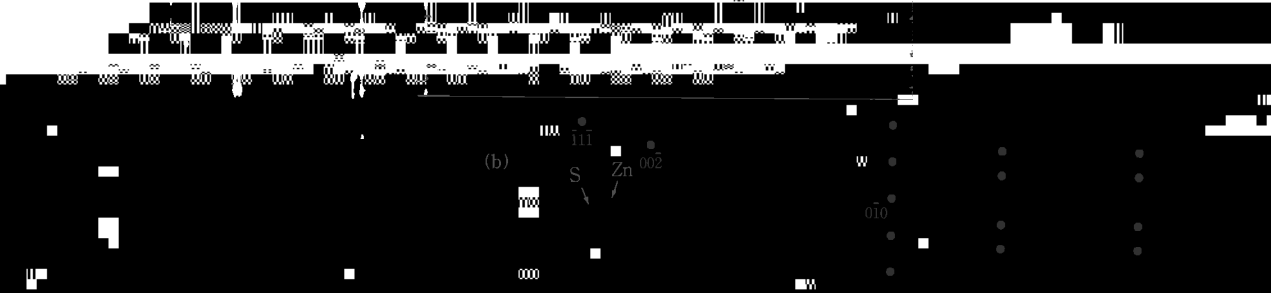
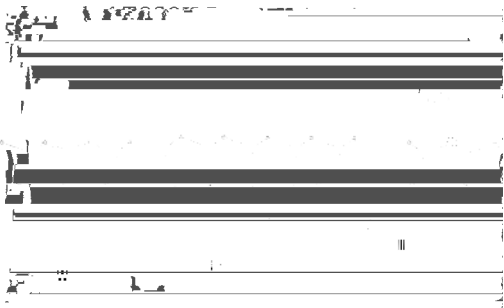


Fig. 9. ZnO diffraction patterns. (a) ZnO; (b) ZnO/S composite.

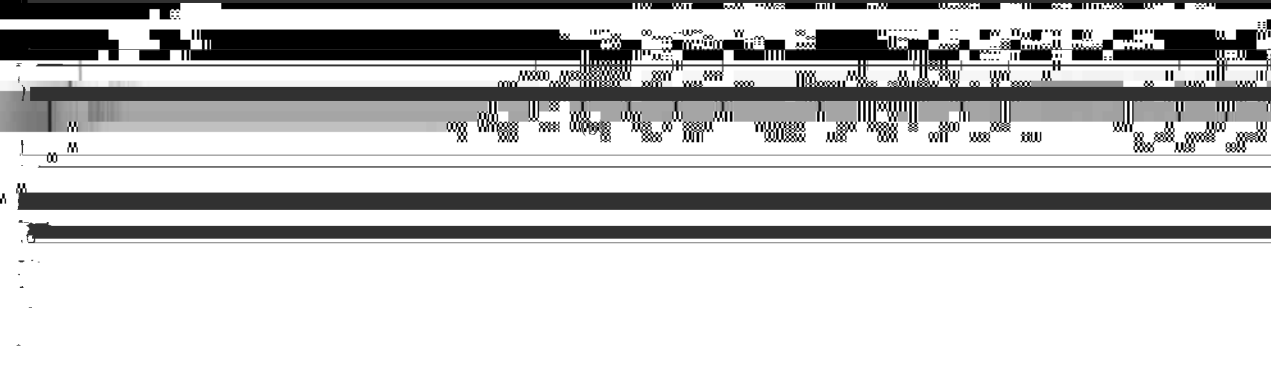
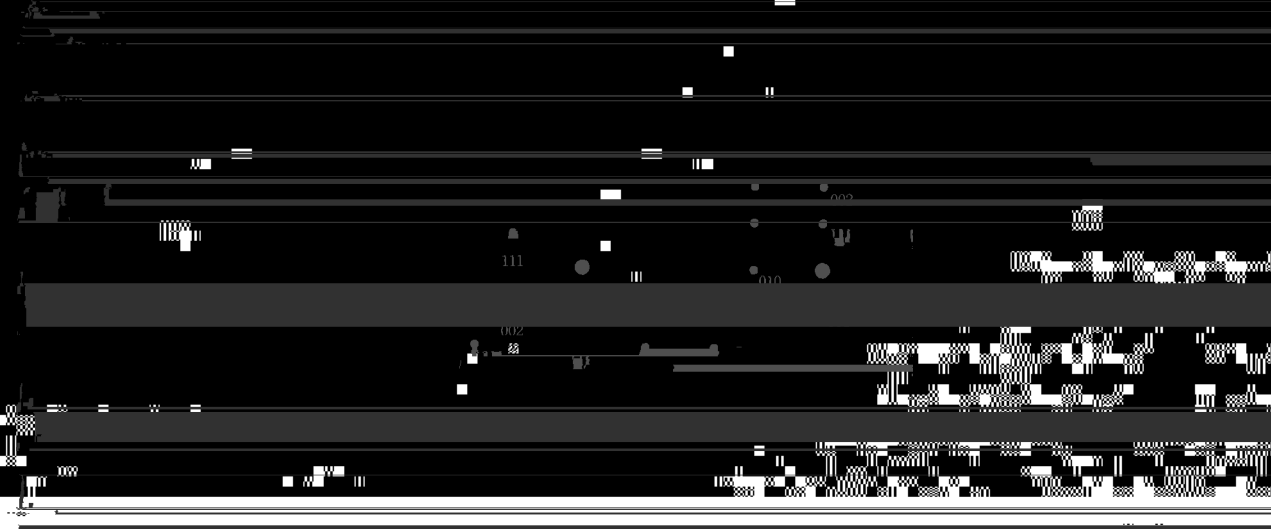


Fig. 10. XRD patterns of ZnO and ZnO/S composite.



This selectivity
 has been shown
 in the case of
 the reaction of
 the above
 with the
 following
 compounds
 and the
 results are
 given in
 Table I.

The results
 show that
 the reaction
 is highly
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 the
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 of the
 product
 and that
 the
 reaction
 is
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 by the
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 of
 water
 or
 other
 impurities.
 The
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 is
 also
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 by the
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 other
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 The
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- a)
- b)
- c)

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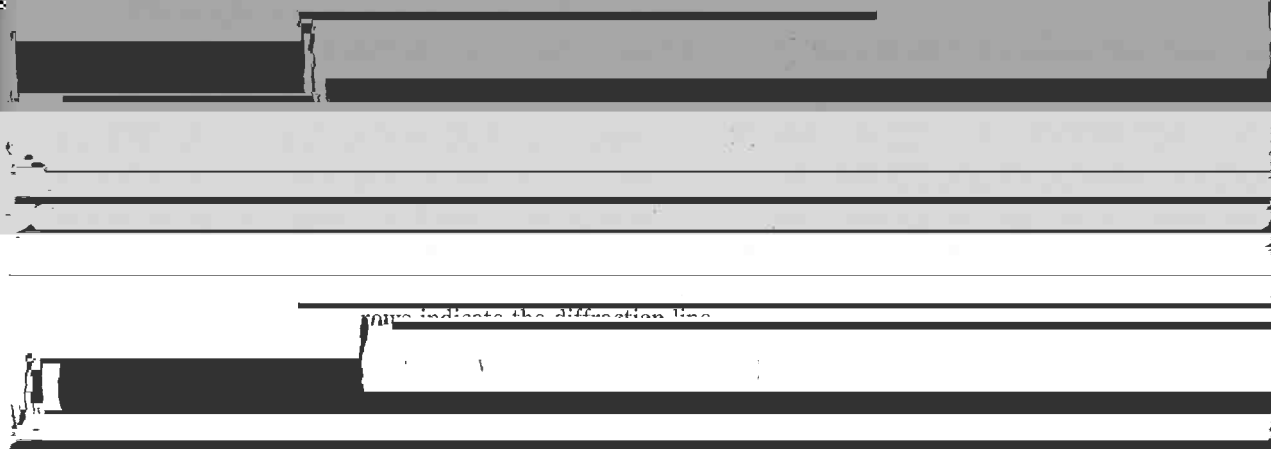
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observations.



mm indicates the diffraction line

- 3) *Com.*
Tokyo
- 4) **References**
- 5) **Microscopic observations and elemental analysis**

RES. 31

KANEYAMA, "Commentary on the ..."

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